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09/420,635 10/21/99 JUENGLING W

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021567 MM91/0122 WELLS ST JOHN ROBERTS GREGORY AND MATKIN SUITE 1300 601 W FIRST AVENUE SPOKANE WA 99201-3828

FILING DATE

APPLICATION NO.

TSAI H
ART UNIT PAPER NUMBER

EXAMINER

2812

DATE MAILED:

01/22/01

ATTORNEY DOCKET NO.

Please find below and/or attached an Office communication concerning this application or proceeding.

Commissioner of Patents and Trademarks

| · · · · · · · · · · · · · · · · · · · | Application No. | Applicant(s) | | | | |
|--|-----------------------------------|-------------------|--|--|--|--|
| | 09/420,635 | JUENGLING, WERNER | | | | |
| Office Action Summary | Examiner | Art Unit | | | | |
| | H. Jey Tsai | 2812 | | | | |
| The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply | | | | | | |
| A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.136 (a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely. - If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication. - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). - Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b). Status | | | | | | |
| 1) Responsive to communication(s) filed on | <u> </u> | | | | | |
| 2a) ☐ This action is FINAL . 2b) ☑ Thi | is action is non-final. | | | | | |
| 3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213. | | | | | | |
| Disposition of Claims | | | | | | |
| 4)⊠ Claim(s) <u>51-53</u> is/are pending in the applicatio | n. | | | | | |
| 4a) Of the above claim(s) is/are withdrawn from consideration. | | | | | | |
| 5) Claim(s) is/are allowed. | | | | | | |
| 6)⊠ Claim(s) <u>51-53</u> is/are rejected. | | | | | | |
| 7) Claim(s) is/are objected to. | | | | | | |
| 8) Claims are subject to restriction and/or election requirement. | | | | | | |
| Application Papers | | | | | | |
| 9) The specification is objected to by the Examiner. | | | | | | |
| 10) The drawing(s) filed on is/are objected t | o by the Examiner. | | | | | |
| 11)☐ The proposed drawing correction filed on is: a)☐ approved b)☐ disapproved. | | | | | | |
| 12) The oath or declaration is objected to by the Examiner. | | | | | | |
| Priority under 35 U.S.C. § 119 | | | | | | |
| 13) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d). | | | | | | |
| a) All b) Some * c) None of: | | | | | | |
| 1. Certified copies of the priority documents | s have been received. | | | | | |
| 2. Certified copies of the priority documents | s have been received in Applicati | on No | | | | |
| 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. | | | | | | |
| 14) Acknowledgement is made of a claim for domestic priority under 35 U.S.C. & 119(e). | | | | | | |
| | | | | | | |
| Attachment(s) | | | | | | |
| 15) Notice of References Cited (PTO-892) 18) Interview Summary (PTO-413) Paper No(s) 19) Notice of Informal Patent Application (PTO-152) 17) Information Disclosure Statement(s) (PTO-1449) Paper No(s) 2 46. 9 18) Interview Summary (PTO-413) Paper No(s) 19) Other: | | | | | | |

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Claim Rejections - 35 U.S.C. § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 51-53 are rejected under 35 U.S.C. § 103 as being unpatentable over Koh et al. 5,686,337 or Chan 5,627,094, both are newly cited, or Rosner 5,496,757 or Kim 5,403,767, both are cited in the parent application.

The reference(s) teach the features:

Koh et al. substantially discloses a method of forming an integrated circuit semiconductor device, which includes :

etching insulating layer 30 to form a capacitor container in first etching step fig. 3,

etching insulating layer 30 to form a capacitor container in second etching step, fig. 5,

forming an insulative partition 30A between the capacitor container with anisotropic etching, fig. 7.

Chan et al. et al. substantially discloses a method of forming an integrated circuit semiconductor device, which includes :

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etching insulating layer 20 to form a capacitor container in first etching step fig. 2b,

etching insulating layer 20 to form a capacitor container in second etching step, fig. 2c,

forming an insulative partition 20b between the capacitor container with anisotropic etching, figs. 2c-2e.

Rosner substantially discloses a method of forming an integrated circuit semiconductor device, which includes:

etching insulating layer 4 to form a capacitor container in first etching step fig. 3,

etching (removing) insulating layer 4 to form a capacitor container in second etching step, figs. 4-5,

forming an insulative partition 81 between the capacitor container fig. 6.

Kim also substantially teaches etching insulating layer 7 to form a capacitor container in first etching step fig. 1C,

etching (removing) insulating layer 7A to form a capacitor container in second etching step, figs. 1E,

forming an insulative partition 9A between the capacitor container figs. 1E-1F.

Any inquiry of a general nature or clerical matters or relating to the status of this application or proceeding should be directed to the Group customer service whose telephone number is (703) 306-3329 and Fax number (703) 306-5515. Group receptionist telephone number 703-308-0956.

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Any inquiry concerning this communication or earlier communications from the examiner should be directed to H. Jey Tsai whose telephone number is (703) 308-1374. The examiner can normally be reached on from 7:00 Am to 4:00 Pm., Monday thru Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, John Niebling can be reached on (703) 308-3325. The fax phone number for this Group is (703) 305-3431.

hjt

01/14/01

Primary Examiner

Patent Examining Group 2800